10688072_CLS
Most Frequently Occurring Classifications of Patents Returned
From A Search of 10688072 on June 16, 2004

Original Classifications

5	250/396R
4	250/492.21
3	250/287
3	250/288
3	250/309
3	250/423R
3	250/427
2	250/398
2	250/492.2
2	315/111.81

Cross-Reference Classifications

9	250/423R
6	250/492.2
4	250/287
4	250/397
4	250/398
3	313/359.1
3	313/363.1
3	315/111.41
3	315/111.81
2	250/281
2	250/288
2	250/307
2	250/310
2	250/396R
2	250/427
2	313/231.31
2	313/362.1
2	315/111.31
2	445/50

Combined Classifications

12	250/423R
8	250/492.2
7	250/287
7	250/396R
6	250/398
5	250/288
5	250/397
5	250/427
5	315/111.81
4	250/492.21

4	313/359.1
3	250/281
3	250/309
3	313/362.1
3	313/363.1
3	315/111.41
2	216/41
2	250/282
2	250/307
2	250/310
2	250/492.3
2	313/231.31
2	315/111.31
2	347/123
2	445/50

10688072_CLSTITLES

Titles of Most Frequently Occurring Classifications of Patents Returned

From A Search of 10688072 on June 16, 2004

12 250/423R (3 OR, 9 XR)
Class 250 : RADIANT ENERGY
250/423R ION GENERATION

8 250/492.2 (2 OR, 6 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices

7 250/287 (3 OR, 4 XR)
Class 250 : RADIANT ENERGY
250/281 IONIC SEPARATION OR ANALYSIS
250/286 .Ion beam pulsing means with detector synchronizing means
250/287 ..With time-of-flight indicator

7 250/396R (5 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR FOCUSSING

6 250/398 (2 OR, 4 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR FOCUSSING
250/398 .With target means

5 250/288 (3 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/281 IONIC SEPARATION OR ANALYSIS
250/288 .With sample supply means

5 250/397 (1 OR, 4 XR)
Class 250 : RADIANT ENERGY
250/396R WITH CHARGED PARTICLE BEAM DEFLECTION OR FOCUSSING
250/397 .With detector

5 250/427 (3 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/423R ION GENERATION
250/427 .Electron bombardment type

5 315/111.81 (2 OR, 3 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL SUPPLY TO THE DISCHARGE SPACE
315/111.81 .Electron or ion source

4 250/492.21 (4 OR, 0 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.2 .Irradiation of semiconductor devices
250/492.21 ..Ion bombardment

4 313/359.1 (1 OR, 3 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION

3 250/281 (1 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/281 IONIC SEPARATION OR ANALYSIS

3 250/309 (3 OR, 0 XR)
Class 250 : RADIANT ENERGY
250/306 INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED PARTICLES
250/309 .Positive ion probe or microscope type

3 313/362.1 (1 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
313/362.1 .Supplying ionizable material (e.g., gas or vapor)

3 313/363.1 (0 OR, 3 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/359.1 WITH POSITIVE OR NEGATIVE ION ACCELERATION
313/363.1 .Extraction or target electrode

3 315/111.41 (0 OR, 3 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL SUPPLY TO THE DISCHARGE SPACE
315/111.21 .Plasma generating
315/111.41 ..With magnetic field

2 216/41 (1 OR, 1 XR)
Class 216 : ETCHING A SUBSTRATE: PROCESSES

216/41 MASKING OF A SUBSTRATE USING MATERIAL RESISTANT TO AN ETCHANT (I.E., ETCH RESIST)

2 250/282 (1 OR, 1 XR)
Class 250 : RADIANT ENERGY
250/281 IONIC SEPARATION OR ANALYSIS
250/282 .Methods

2 250/307 (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/306 INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED PARTICLES
250/307 .Methods

2 250/310 (0 OR, 2 XR)
Class 250 : RADIANT ENERGY
250/306 INSPECTION OF SOLIDS OR LIQUIDS BY CHARGED PARTICLES
250/310 .Electron probe type

2 250/492.3 (1 OR, 1 XR)
Class 250 : RADIANT ENERGY
250/492.1 IRRADIATION OF OBJECTS OR MATERIAL
250/492.3 .Ion or electron beam irradiation

2 313/231.31 (0 OR, 2 XR)
Class 313 : ELECTRIC LAMP AND DISCHARGE DEVICES
313/231.01 FLUENT MATERIAL SUPPLY OR FLOW DIRECTING MEANS

313/231.31 .Plasma

2 315/111.31 (0 OR, 2 XR)
Class 315 : ELECTRIC LAMP AND DISCHARGE DEVICES: SYSTEMS

315/111.01 DISCHARGE DEVICE LOAD WITH FLUENT MATERIAL SUPPLY TO THE DISCHARGE SPACE
315/111.21 .Plasma generating
315/111.31 ..With extraction electrode

2 347/123 (1 OR, 1 XR)
Class 347 : INCREMENTAL PRINTING OF SYMBOLIC INFORMATION

347/111 ELECTRIC MARKING APPARATUS OR PROCESSES
347/112 .Electrostatic
347/120 ..By information carrying flow of invisible charged particles
347/123 ...Specific ionographic head

2 445/50 (0 OR, 2 XR)

Class	445 : ELECTRIC LAMP OR SPACE DISCHARGE COMPONENT OR DEVICE MANUFACTURING
445/1	PROCESS
445/46	.Electrode making
445/49	..Electrode shaping
445/50	...Emissive type